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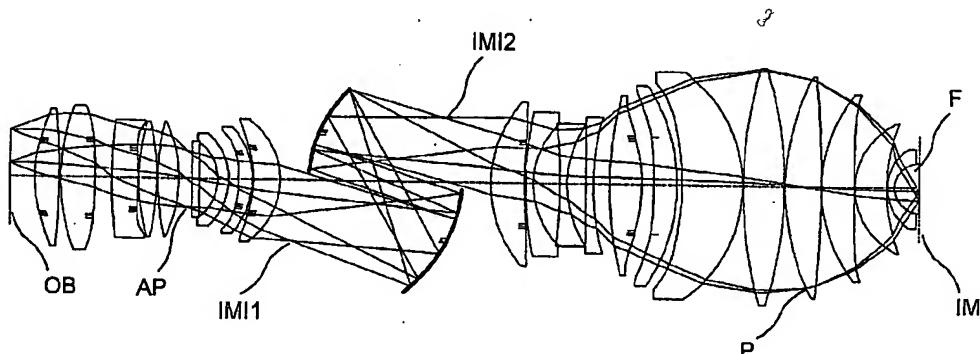
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[Continued on next page]

(54) Title: OBJECTIVE AS A MICROLITHOGRAPHY PROJECTION OBJECTIVE WITH AT LEAST ONE LIQUID LENS



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(57) Abstract: The invention relates to an objective designed as a microlithography projection objective for an operating wavelength. The objective has a greatest adjustable image-side numerical aperture NA, at least one first lens made from a solid transparent body, in particular glass or crystal, with a refractive index n_L and at least one liquid lens (F) made from a transparent liquid, with a refractive index n_F . At the operating wavelength the first lens has the greatest refractive index n_L of all solid lenses of the objective, the refractive index n_F of the at least one liquid lens (F) is bigger than the refractive index n_L of the first lens and the value of the numerical aperture NA is bigger than 1.



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